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APPLICATION NO. FILING DATE FIRST NAMED INVENTOR ATTORNEY DOCKET NO. CONFIRMATION NO. 10/815,068 03/26/2004 Karson L. Knutson 110348-134668 8657 25943 7590 12/17/2004 EXAMINER SCHWABE, WILLIAMSON & WYATT, P.C. FUQUA, SHAWNTINA T PACWEST CENTER, SUITES 1600-1900 ART UNIT PAPER NUMBER 1211 SW FIFTH AVENUE PORTLAND, OR 97204 3742

DATE MAILED: 12/17/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

| | | | | K |
|--|--|----------------------------|--|-----|
| | | Application No. | Applicant(s) | p |
| Office Action Summary | | 10/815,068 | KNUTSON ET AL. | 1 |
| | | Examiner | Art Unit | |
| | | Shawntina T. Fuqua | 3742 | |
| Period fo | The MAILING DATE of this communication apported by the second section apports and the second section apport | pears on the cover sheet v | vith the correspondence addr | ess |
| A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). | | | | |
| Status | , | | | |
| 1) | Responsive to communication(s) filed on 26 M | larch 2004 | | |
| · | This action is FINAL . 2b)⊠ This action is non-final. | | | |
| | 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. | | | |
| · | | | | |
| Disposit | ion of Claims | | | |
| 5)□ 6)⊠ 7)□ | 4) | | | |
| Applicati | ion Papers | | | ` |
| 9) ☐ The specification is objected to by the Examiner. 10) ☑ The drawing(s) filed on 26 March 2004 is/are: a) ☑ accepted or b) ☐ objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152. | | | | |
| Priority ι | under 35 U.S.C. § 119 | | | |
| 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. | | | | |
| Attachmen | at(s) | | | |
| 1) 🛛 Notic | ce of References Cited (PTO-892) | | Summary (PTO-413) | |
| 3) 🔲 Infor | ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) er No(s)/Mail Date | | (s)/Mail Date Informal Patent Application (PTO-1 | 52) |

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DETAILED ACTION

Specification

1. Applicant is reminded of the proper content of an abstract of the disclosure.

A patent abstract is a concise statement of the technical disclosure of the patent and should include that which is new in the art to which the invention pertains. If the patent is of a basic nature, the entire technical disclosure may be new in the art, and the abstract should be directed to the entire disclosure. If the patent is in the nature of an improvement in an old apparatus, process, product, or composition, the abstract should include the technical disclosure of the improvement. In certain patents, particularly those for compounds and compositions, wherein the process for making and/or the use thereof are not obvious, the abstract should set forth a process for making and/or use thereof. If the new technical disclosure involves modifications or alternatives, the abstract should mention by way of example the preferred modification or alternative.

The abstract should not refer to purported merits or speculative applications of the invention and should not compare the invention with the prior art.

Where applicable, the abstract should include the following:

- (1) if a machine or apparatus, its organization and operation;
- (2) if an article, its method of making;
- (3) if a chemical compound, its identity and use;
- (4) if a mixture, its ingredients;
- (5) if a process, the steps.

Extensive mechanical and design details of apparatus should not be given.

2. Applicant is reminded of the proper language and format for an abstract of the disclosure.

The abstract should be in narrative form and generally limited to a single paragraph on a separate sheet within the range of 50 to 150 words. It is important that the abstract not exceed 150 words in length since the space provided for the abstract on the computer tape used by the printer is limited. The form and legal phraseology often used in patent claims, such as "means" and "said," should be avoided. The abstract should describe the disclosure sufficiently to assist readers in deciding whether there is a need for consulting the full patent text for details.

The language should be clear and concise and should not repeat information given in the title. It should avoid using phrases which can be implied, such as, "The disclosure concerns," "The disclosure defined by this invention," "The disclosure describes," etc.

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3. The abstract of the disclosure is objected to because lines 1-2 repeat information given in the title. Correction is required. See MPEP § 608.01(b).

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 1-3, 5-7, 11-15, and 20-24 are rejected under 35 U.S.C. 103(a) as being unpatentable over Thakur (US6808758) in view of O'Carroll et al (US6559424) and Liu et al (US6385396).

Thakur discloses an apparatus/method/system comprising a semiconductor wafer as a target area (22), lamps (27), a reflective device (column 5, lines 1-3), a backside hotplate as a heating device (34), and a system which includes multichambers (column 9, lines 6-14). Thakur does disclose flash lamps, a reflective device having a plurality of concentric zones wherein each is associated with a reflectivity, and a plate type reflector wherein the zones are symmetrical around a vertical axis. O'Carroll et al discloses flash lamps (column 3, lines 57-65) and Liu et al discloses a reflective device (6, 7, 8) having a plurality of concentric zones wherein each is associated with a reflectivity (column 3, lines 16-54), and a plate type reflector wherein the zones are symmetrical around a vertical axis (Figure 3). It would have been obvious to one of ordinary skill in the art at the time the invention was made to have replaced the lamps and reflector of Thakur with the flash lamps of O'Carroll and the reflector of Liu et al because, flash

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lamps and a zonal reflector allow the temperature to be controlled more accurately and allow for a more uniform heating.

6. Claims 4, , 16, and 24 are rejected under 35 U.S.C. 103(a) as being unpatentable over Thakur in view of O'Carroll et al and Liu et al as applied to claims 1, 13, and 20 above, and further in view of Lee et al (US6753272).

Thakur in view of O'Carroll et al and Liu et al discloses all of the recited subject matter except a heating plate with independently controlled zones. Lee et al discloses a heating plate with independently controlled zones (40, abstract). It would have been obvious to one of ordinary skill in the art at the time the invention was made to have included the heating plate with independently controlled zones of Lee et al in the apparatus of Thakur along with the flash lamps O'Carroll et al and reflector of Liu et al because, independently controlled zones allows the wafer to be uniformly heated and prevents slip line formations.

7. Claim is rejected under 35 U.S.C. 103(a) as being unpatentable over Thakur in view of O'Carroll et al and Liu et al as applied to claim 1 above, and further in view of Gat et al (US6771895).

Thakur in view of O'Carroll et al and Liu et al discloses all of the recited subject matter except a gold reflector. Gat et al discloses using gold as a reflector (column 4, lines 38-40). It would have been obvious to one of ordinary skill in the art at the time the invention was made to have included gold as a reflector as taught by Gat et al in the apparatus of Thakur along with the flash lamps of O'Carroll et al and reflector of Liu et al because, a gold reflector allows the wafer to be heated more uniformly.

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8. Claims 9-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Thakur in view of O'Carroll and Liu et al as applied to claim 1 above, and further in view of Grant et al (US5228206).

Thakur in view of O'Carroll et al and Liu et al discloses all of the recited subject matter except a xenon flash lamp. Grant et al discloses a xenon flash lamp (abstract). It would have been obvious to one of ordinary skill in the art at the time the invention was made to have included a xenon flash lamp in the apparatus of Thakur along with the flash lamps of O'Carroll et al and reflector of Liu et al because, a xenon flash lamp allows the substrate to be heated more efficiently.

9. Claims 17-19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Thakur in view of O'Carroll et al and Liu et al as applied to claims 13 and 15 above, and further in view of Noguchi (US5219786).

Thakur in view of O'Carroll et al and Liu et al discloses all of the recited subject matter except activating implanted ions by heating the second surface to a pre-flash temperature below ion diffusion and heating a first surface to a temperature between ion diffusion and substrate melting by light rays from a flash lamp and the first surface is above the ion diffusion temperature for a time period of three milliseconds or less. Noguchi discloses activating implanted ions by heating the second surface to a pre-flash temperature below ion diffusion and heating a first surface to a temperature between ion diffusion and substrate melting by light rays from a flash lamp and the first surface is above the ion diffusion temperature for a time period of three milliseconds or less (column 2, line 31-column 3, line 60). It would have been obvious to one of ordinary skill in the art at the time the invention was made to have included the activating

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implanted ions heating method of Noguchi in the apparatus of Thakur along with the flash lamps of O'Carroll et al and reflector of Liu et al because, activating implanted ions by heating the second surface to a pre-flash temperature below ion diffusion and heating a first surface to a temperature between ion diffusion and substrate melting by light rays from a flash lamp and the first surface is above the ion diffusion temperature for a time period of three milliseconds or less allows a semiconductor layer to be formed on the substrate at a relatively high temperature while the substrate carrying the layer is heated at a temperature that will not cause adverse effects on the substrate.

Conclusion

10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shawntina T. Fuqua whose telephone number is (703) 305-2581. The examiner can normally be reached on Monday-Friday 8-4:30 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Robin Evans can be reached on (703) 305-5766. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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stf

November 12, 2004

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Shawntina Fuqua

Patent Examiner

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